

SHIGA7.054APC

10/589681  
10/589681  
13 AUG 2006

PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant : Ogata et al.  
Appl. No. : U.S. National Phase of  
PCT/JP2005/001228  
Filed : Herewith  
For : POLYMER COMPOUND,  
PHOTORESIST COMPOSITION  
INCLUDING THE POLYMER  
COMPOUND, AND RESIST  
PATTERN FORMATION  
METHOD  
Examiner : Unassigned  
Group Art Unit : Unknown

CERTIFICATE OF MAILING

I hereby certify that this correspondence and all marked attachments are being deposited with the United States Postal Service as first-class mail in an envelope addressed to: Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450, on

August 16, 2006

(Date)

Neil S. Barfield, Ph.D., Reg. No. 39,901

**PRELIMINARY AMENDMENT**

**Mail Stop PCT**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Dear Sir:

Prior to examination of the above-referenced application, please enter the following amendments:

**Amendments to the Specification** begin on page 2 of this paper.

**Amendments to the Claims** begin on page 3 of this paper.

**Remarks** begin on page 8 of this paper.